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LINDA E. HASTINGS

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Attorney Docket No.: NECF 17.638B (100806-00233)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: Mami MIYASAKA

Serial No.: 10/657,429

Confirmation No.: 9031

Filed: September 8, 2003

Title: **ELECTRON BEAM EXPOSURE MASK, ELECTRON BEAM EXPOSURE METHOD, METHOD OF FABRICATING SEMICONDUCTOR, AND ELECTRON BEAM EXPOSURE APPARATUS**

Examiner: Anthony G. Quash

Group Art Unit: 2881

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT UNDER 37 C.F.R. §1.312

S I R :

Pursuant to 37 C.F.R. §1.312, it is respectfully requested that the following amendment be entered, this amendment being filed before or on the date of payment of the Issue Fee: